## **Tutorial 2 solutions**

**Q. 1)** Consider a non- parabolic band structure satisfying the relation  $E(1 + \alpha E) = \frac{\hbar^2 k^2}{2m_o}$ . Find the wave packet group velocity for the given band structure for large energies. (Assume  $\alpha$  to be close to 1).

**Sol)** For large energies, E>>1/ $\alpha$  or  $\alpha$ E>>1 =>  $\alpha E^2 = \frac{\hbar^2 k^2}{2m_o}$  or E=  $\frac{\hbar k}{\sqrt{2m_o\alpha}}$ . The wave packet group velocity,  $v_g = \frac{dE}{\hbar dk} = \frac{1}{\sqrt{2m_o\alpha}}$ .

Q. 2) Find the density of states (DOS) expression for 2-dimensional (2D) material.

**Sol)** States between E+ $\Delta$ E and E, dn=2 ( $spin\ degeneracy$ ) \*  $\frac{\pi(k+dk)^2-\pi k^2}{\frac{2\pi}{L}*W}=\frac{Akdk}{\pi}$ .

States per unit energy per unit area =  $\frac{dn}{dE} = \frac{k}{\pi} \left( \frac{dk}{dE} \right)$  and  $\frac{dk}{dE} = \frac{1}{\hbar} \sqrt{\frac{m^*}{2E}}$ 

because  $E=rac{\hbar^2 k^2}{2m^*}$  or  $k=rac{\sqrt{2m^*E}}{\hbar}$ . This gives DOS,  $g_c=rac{\sqrt{2m^*E}}{\pi\hbar} imesrac{1}{\hbar}\sqrt{rac{m^*}{2E}}=rac{m^*}{\pi\hbar^2}$ .

**Q. 3)** Calculate the position of Fermi level at room temperature (w.r.t. bottom of conduction band) in crystalline silicon doped with phosphorus atoms having doping concentrations:

Note: Use  $N_C = 2.81 \times 10^{19}$  cm<sup>-3</sup> for silicon.

**Sol)** For n-type semiconductor, n^N\_D =>  $n = N_C \, e^{-\frac{(E_C - E_F)}{k_B T}} \cong N_D$ .

At room temperature, k<sub>B</sub>T = 0.026 eV,  $\therefore$   $E_C-E_F=0.026 \ln \frac{2.81\times 10^{19}}{N_D}$ 

a) 
$$E_C - E_F = 0.026 \ln \frac{2.81 \times 10^{19}}{10^{16}} = 0.206 \text{ eV}$$

b) 
$$E_C - E_F = 0.026 \ln \frac{2.81 \times 10^{19}}{10^{17}} = 0.146 \text{ eV}$$

c) 
$$E_C - E_F = 0.026 \ln \frac{2.81 \times 10^{19}}{10^{18}} = 0.087 \text{ eV}$$

Q. 4) Find the electron density in a 3D electron gas at T = 0 K in terms of Fermi energy, E<sub>F</sub>.

Sol) States between E+ $\Delta$ E and E, dn=2 ( $spin\ degeneracy$ ) \*  $\frac{\frac{4}{3}\pi(k+dk)^3-\frac{4}{3}\pi k^3}{\frac{2\pi}{L}*\frac{2\pi}{W}*\frac{2\pi}{H}}=\frac{Vk^2dk}{\pi^2}$ .

=> 
$$n = \int_0^{k_F} \frac{V k^2 dk}{\pi^2} = \frac{V k^3}{3\pi^2}$$
. We know that,  $E_F = \frac{\hbar^2 k_F^2}{2m}$  which gives  $n = \frac{V(2mE_F)^{\frac{3}{2}}}{3\pi^2 \hbar^3}$ .

Therefore, the electron density is:  $n = \frac{(2mE_F)^{\frac{3}{2}}}{3\pi^2\hbar^3}$ .

**Q. 5)** If both silicon and germanium are doped with  $N_D = 5 \times 10^{14}$  cm<sup>-3</sup> each, find their respective intrinsic carrier concentration at T = 400 K. Comment on the nature of the semiconductors at 400 K. Use  $E_{g,Si} = 1.12$  eV,  $E_{g,Ge} = 0.66$  eV,  $n_{i,Si}^{300K} = 1.5 \times 10^{10}$  cm<sup>-3</sup> and  $n_{i,Ge}^{300K} = 2.5 \times 10^{13}$  cm<sup>-3</sup>.

**Sol)** We know that,  $n_i = \sqrt{N_c N_v} e^{-\frac{E_g}{2k_BT}} = 2\left(\frac{2\pi k_BT}{\hbar^2}\right)^3 (m_n^* m_h^*)^{\frac{3}{2}} e^{-\frac{E_g}{2k_BT}}$ . Hence by comparing  $n_i$  values at different temperatures,

For Si:

$$\frac{n_{l,Si}^{400K}}{n_{l,Si}^{300K}} = \left(\frac{400}{300}\right)^{\frac{3}{2}} e^{-\frac{0.66 \times 1.6 \times 10^{-19}}{2 \times 1.38 \times 10^{-23}} \left(\frac{1}{400} - \frac{1}{300}\right)} = 344.52$$

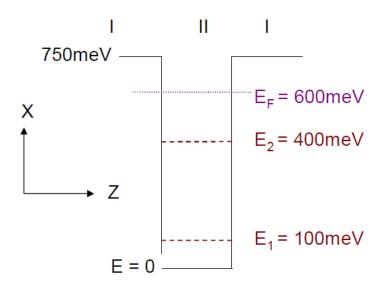
$$=> n_{i,Si}^{400K} = 344.52 \times 1.5 \times 10^{10} \text{ cm}^{-3} = 5.17 \times 10^{12} \text{ cm}^{-3} < N_D => \text{n-type}$$

For Ge:

$$\frac{n_{i,Ge}^{400K}}{n_{i,Ge}^{300K}} = \left(\frac{400}{300}\right)^{\frac{3}{2}} e^{-\frac{0.66 \times 1.6 \times 10^{-19}}{2 \times 1.38 \times 10^{-23}} \left(\frac{1}{400} - \frac{1}{300}\right)} = 24.25$$

$$=> n_{i,Ge}^{400K} = 24.25 \times 2.5 \times 10^{13} \text{ cm}^{-3} = 6.06 \times 10^{14} \text{ cm}^{-3} > N_D => intrinsic$$

**Q. 6)** Given that  $g_{2D}=\frac{m_o}{\pi\hbar^2}\sim 4.2\times 10^{16}cm^{-2}eV^{-1}$  and a quasi 2D system where a quantum well in the heterostructure formed by semiconductors I and II is shown as:

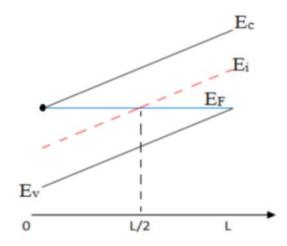


Find the 2D electron density at cryogenic temperature.

**Sol)** Cryogenic temperature means a very low temperature (not well defined but usually defined at 123 K)

$$n = \int g_c(E)f(E)dE = \int_0^{600 \, meV} \frac{m_o}{\pi \hbar^2} dE = \frac{m_o}{\pi \hbar^2} ((E_F - E_1) + (E_F - E_2))$$
  
=>  $n = 4.2 \times 10^{16} \times (500 + 200) \times 10^{-3} cm^{-2} = 2.94 \times 10^{16} \, cm^{-2}$ 

**Q. 7)** For the band diagram given below, answer the following questions:



- a) Is the semiconductor in equilibrium? Justify.
- b) Sketch the electrostatic potential, electric field, potential and kinetic energies as a function of x inside the semiconductor.

Assume  $E_F$  as the reference level and particle shown in solid circle moves back and forth between x = 0 and x = L without changing the total energy.

## Sol) a) Yes because Fermi level straight

b) minimum voltage is taken as zero. The offset can be taken as any value without affecting the shape and relative change in potential. E<sub>F</sub> is taken as reference energy for calculating kinetic energy (KE) and potential energy (PE).

